

United States Patent and Trademark Office

oh

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO. FILING DATE		FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
10/710,870	10/710,870 08/09/2004		Dennis W. Prather	00131-00322-US1	4869	
30678	7590	01/23/2006		EXAMINER		
		E LODGE & HUTZ	LEE, CALVIN			
SUITE 800 1990 M STREET NW				ART UNIT	PAPER NUMBER	
WASHING	TON, DC	20036-3425	2818			
				DATE MAILED: 01/23/2006		

Please find below and/or attached an Office communication concerning this application or proceeding.

Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)	
10/710,870	PRATHER et al.	
Examiner	Art Unit	
Lee, Calvin	2818	

Before the filling of all Appear Brief	Examiner	Art Unit						
	Lee, Calvin	2818						
The MAILING DATE of this communication appe	ars on the cover sheet with the c	correspondence add	ress					
THE REPLY FILED 27 December 2005 FAILS TO PLACE THIS APPLICATION IN CONDITION FOR ALLOWANCE.								
1. ☑ The reply was filed after a final rejection, but prior to or on the same day as filing a Notice of Appeal. To avoid abandonment of this application, applicant must timely file one of the following replies: (1) an amendment, affidavit, or other evidence, which places the application in condition for allowance; (2) a Notice of Appeal (with appeal fee) in compliance with 37 CFR 41.31; or (3) a Request for Continued Examination (RCE) in compliance with 37 CFR 1.114. The reply must be filed within one of the following time periods:								
b) The period for reply expires on: (1) the mailing date of this Adv	The period for reply expires 3 months from the mailing date of the final rejection. The period for reply expires on: (1) the mailing date of this Advisory Action, or (2) the date set forth in the final rejection, whichever is later. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of the final rejection.							
Examiner Note: If box 1 is checked, check either box (a) or (b). ONLY CHECK BOX (b) WHEN THE FIRST REPLY WAS FILED WITHIN TWO MONTHS OF THE FINAL REJECTION. See MPEP 706.07(f).								
Extensions of time may be obtained under 37 CFR 1.136(a). The date on which the petition under 37 CFR 1.136(a) and the appropriate extension fee have been filed is the date for purposes of determining the period of extension and the corresponding amount of the fee. The appropriate extension fee under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the shortened statutory period for reply originally set in the final Office action; or (2) as set forth in (b) above, if checked. Any reply received by the Office later than three months after the mailing date of the final rejection, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). NOTICE OF APPEAL								
2. The Notice of Appeal was filed on A brief in compliance with 37 CFR 41.37 must be filed within two months of the date of filing the Notice of Appeal (37 CFR 41.37(a)), or any extension thereof (37 CFR 41.37(e)), to avoid dismissal of the appeal. Since a Notice of Appeal has been filed, any reply must be filed within the time period set forth in 37 CFR 41.37(a).								
<u>AMENDMENTS</u>								
The proposed amendment(s) filed after a final rejection, but prior to the date of filing a brief, will <u>not</u> be entered because (a) They raise new issues that would require further consideration and/or search (see NOTE below); (b) They raise the issue of new matter (see NOTE below); (c) They are not deemed to place the application in better form for appeal by materially reducing or simplifying the issues for								
appeal; and/or (d) They present additional claims without canceling a			g the issues for					
NOTE: (See 37 CFR 1.116 and 41.33(a)).	•	•						
4. The amendments are not in compliance with 37 CFR 1.121. See attached Notice of Non-Compliant Amendment (PTOL-324).								
5. Applicant's reply has overcome the following rejection(s): 6. Newly proposed or amended claim(s) would be allowable if submitted in a separate, timely filed amendment canceling the non-allowable claim(s).								
7. For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is pro The status of the claim(s) is (or will be) as follows:	· · · · · · · · · · · · · · · · · · ·	vill be entered and an	explanation of					
Claim(s) allowed: Claim(s) objected to:		•	•					
Claim(s) rejected: Claim(s) withdrawn from consideration:		•						
AFFIDAVIT OR OTHER EVIDENCE								
8. The affidavit or other evidence filed after a final action, be because applicant failed to provide a showing of good an and was not earlier presented. See 37 CFR 1.116(e).	-	• • • • • • • • • • • • • • • • • • • •						
9. The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to a showing a good and sufficient reasons why it is necessar	overcome <u>all</u> rejections under appe y and was not earlier presented. S	al and/or appellant fa See 37 CFR 41.33(d)(ils to provide a (1).					
10. The affidavit or other evidence is entered. An explanation REQUEST FOR RECONSIDERATION/OTHER	on of the status of the claims after e	entry is below or attac	ched.					
11. The request for reconsideration has been considered by	it does NOT place the application i	n condition for allowa	ance because:					
12. Note the attached Information Disclosure Statement(s).	(PTO/SB/08 or PTO-1449) Paper	No(s)						
13. Other: David Nolms								
Cupon	David Nelms							
	visory Patent Examiner Inology Center 2800							
1661	mology officer ZOUU							

U.S. Patent and Trademark Office

PTOL-303 (Rev. 7-05)

Continuation of 11. does NOT place the application in condition for allowance because:

Disk 50 (in Lin et al '342) not only squeezes off excessive paste 30 but also polishes the paste (using its flat surface) to level with that of the photoresist layer 15 [Fig. 4]. Therefore, the polymer paste has been polished from the surface of the photoresist.

Nevertheless, such polishing of a polymer is known in the semiconductor processing art as evidenced by Applicant's Prior Art disclosing, "...scraping and dispensing the polymer material by use of a polishing technique" [paragraph 0010].

David Nelms
Supervisory Patent Examiner
Technology Center 2800